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Please amend claim 1 as follows.

Sub D

1. (Amended) A plasma CVD apparatus comprising:

Sub D

a vacuum chamber;

Sub D

an introducing means for introducing a gas into the vacuum chamber;

an exhaust means for exhausting the gas from the vacuum chamber to an outside;

a first electrode for supplying an electric energy inside the vacuum chamber;

A1

a supporting means for supporting a substrate opposing the first electrode,

wherein an introducing port is located adjacent to an electrode side surface of the substrate,

wherein a plurality of openings are located on a surface of the first electrode opposing the substrate,

wherein the gas is exhausted from the plurality of openings to the outside of the vacuum chamber.

Please add new claims 6-8.

A2

6. An apparatus according to claim 1 further comprising:

a second electrode opposing the first electrode for supplying the electric energy inside the vacuum chamber.

Sub D

7. An apparatus according to claim 6,

wherein the substrate is supported between the first and second electrodes by the supporting means.

8. An apparatus according to claim 2,

A2
cut
wherein the transporting means includes at least one selected from the group consisting of an unwinding roll and a *D₁* winding roll.

A&B >
D₂